

# **Fine Pitch Substrate for Cost Effective Flip Chip Package using Embedded Trace Substrate Technology**

***Dr. Kay Essig***

**ASE Europe  
May 21, 2014**



# EPP Substrates

- ASE Substrate Manufacturing
- Substrate manufacturing
  - Subtractive
  - MSAP/ SAP
  - EPP
- Cu pillar FlipChip fine pitch
  - Peripheral, Array, Pitches on Substrate
  - Reliability Results
- Wire Bond Finger Pitch (Hybrids)
- Conclusion



# Substrate Manufacturing Sites

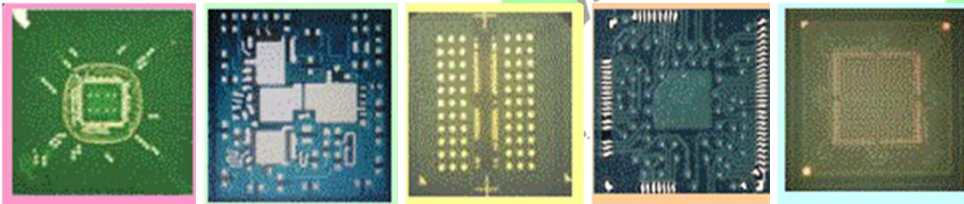
## ASEMTL Shanghai outlook

- Operation began from 2003
- Capital: \$140M USD
- Revenue : 2010: \$205M    2011: \$185M    2012: \$200M
- Capacity: 48kk pcs /Month based on PKG(27x27mm)
- Manpower : 1,750
  - Manufacture: 1300
  - PE, RD & QA: 280

ASEMTL  
Shanghai,  
China



ASEMTL  
Kaohsiung,  
Taiwan



PBGA

Module

BOC

TFBGA

FCCSP

# Substrate Manufacturing Sites

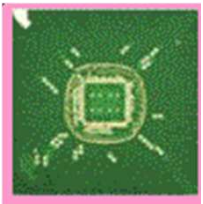
## ASEMTL Kaohsiung outlook

- Operation began from 1995
- Capital: \$135M USD
- Revenue : 2010: \$110M    2011: \$125M    2012: \$140M
- Capacity: 22kk pcs /Month based on PKG(27x27mm)  
( future expansion to 36kk pcs/Month )
- Manpower : 1,000
  - Manufacture: 650
  - PE, RD & QA: 250

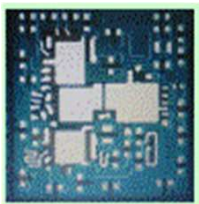
ASEMTL  
Shanghai,  
China



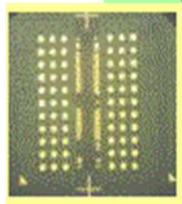
ASEMTL  
Kaohsiung,  
Taiwan



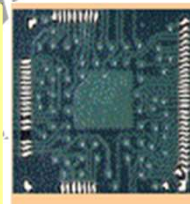
PBGA



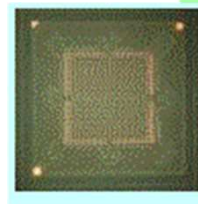
Module



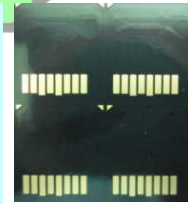
BOC



TFBGA



FCCSP

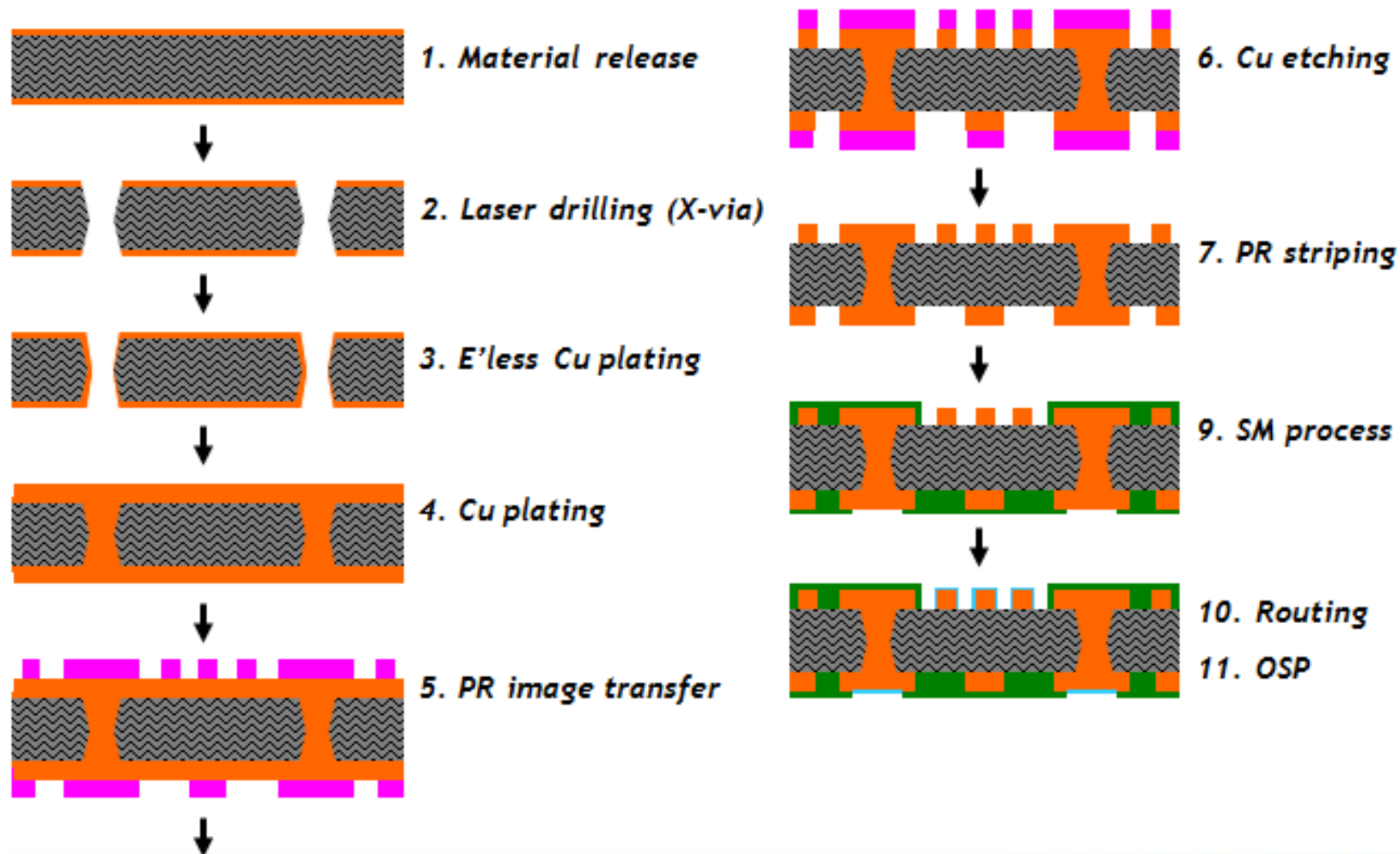


HG

# Substrate manufacturing

## ○ Subtractive

- Via drill, E'less Cu, Panel Plating, Tent'n'Etch

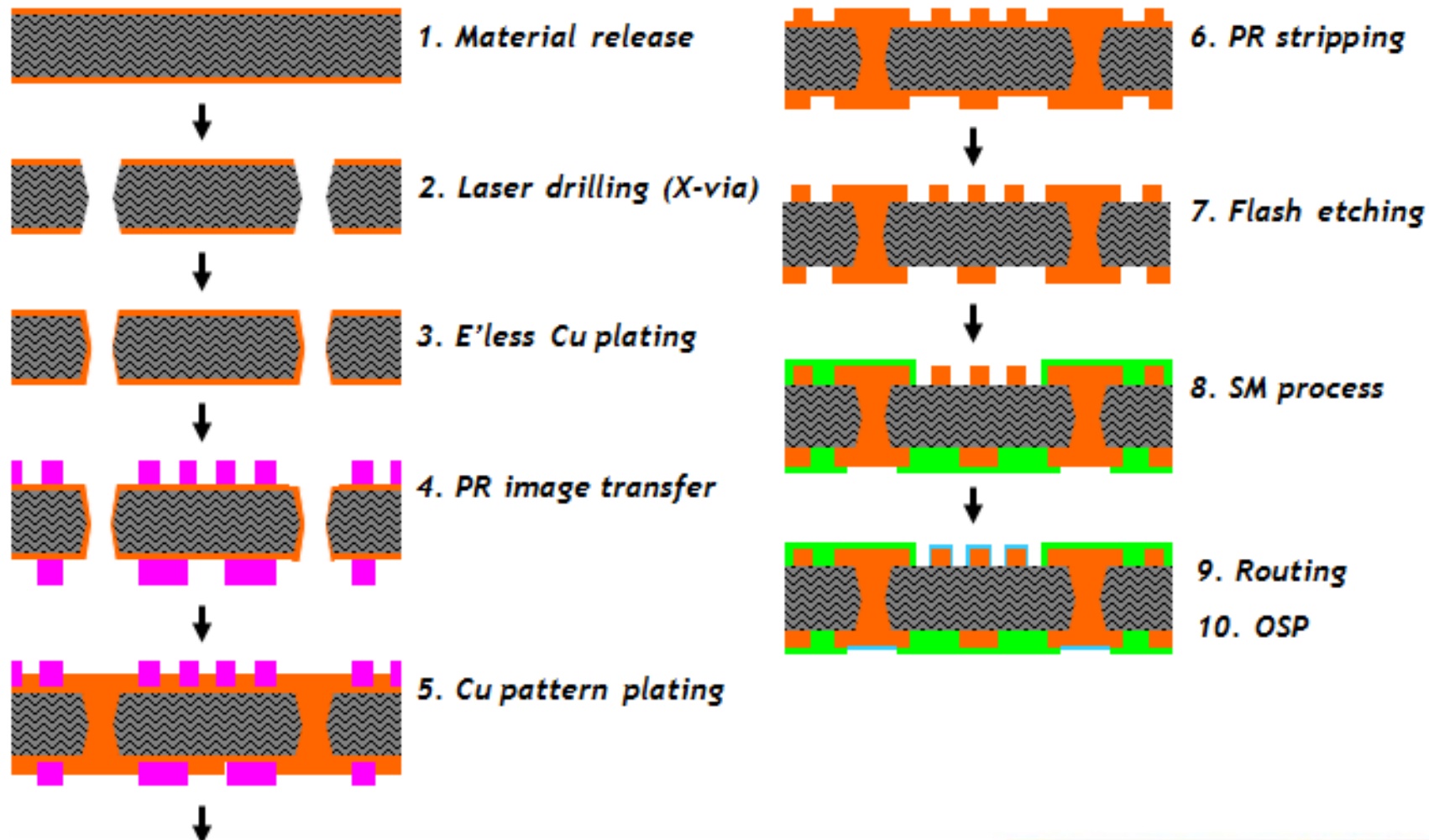




# Substrate manufacturing

## • MSAP (Modified Semi Additive Process), SAP

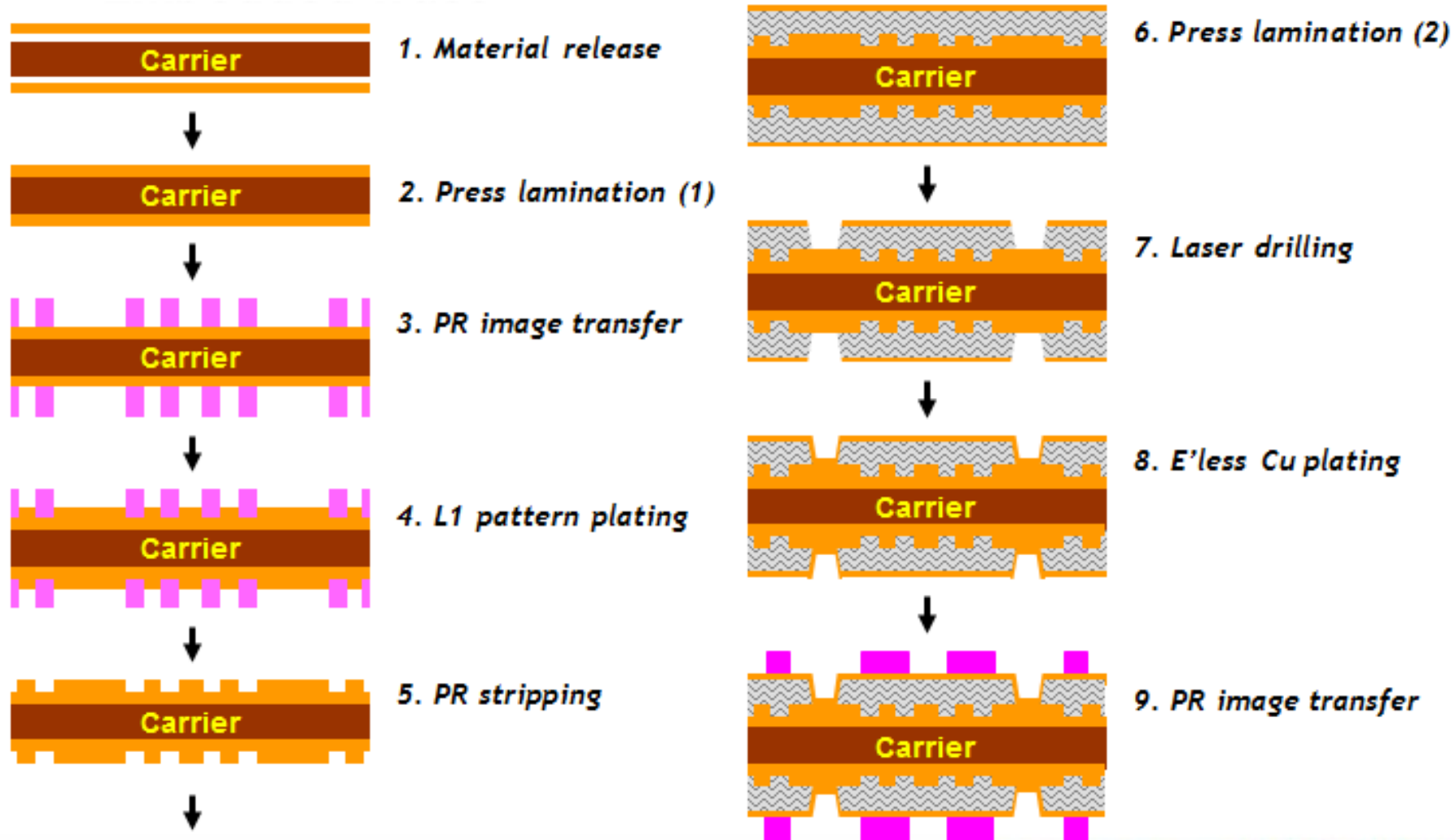
- Via drill, E'less Cu, Pattern Plating, Flash Etch



# Substrate manufacturing

## ● EPP (Embedded Pattern Process) I

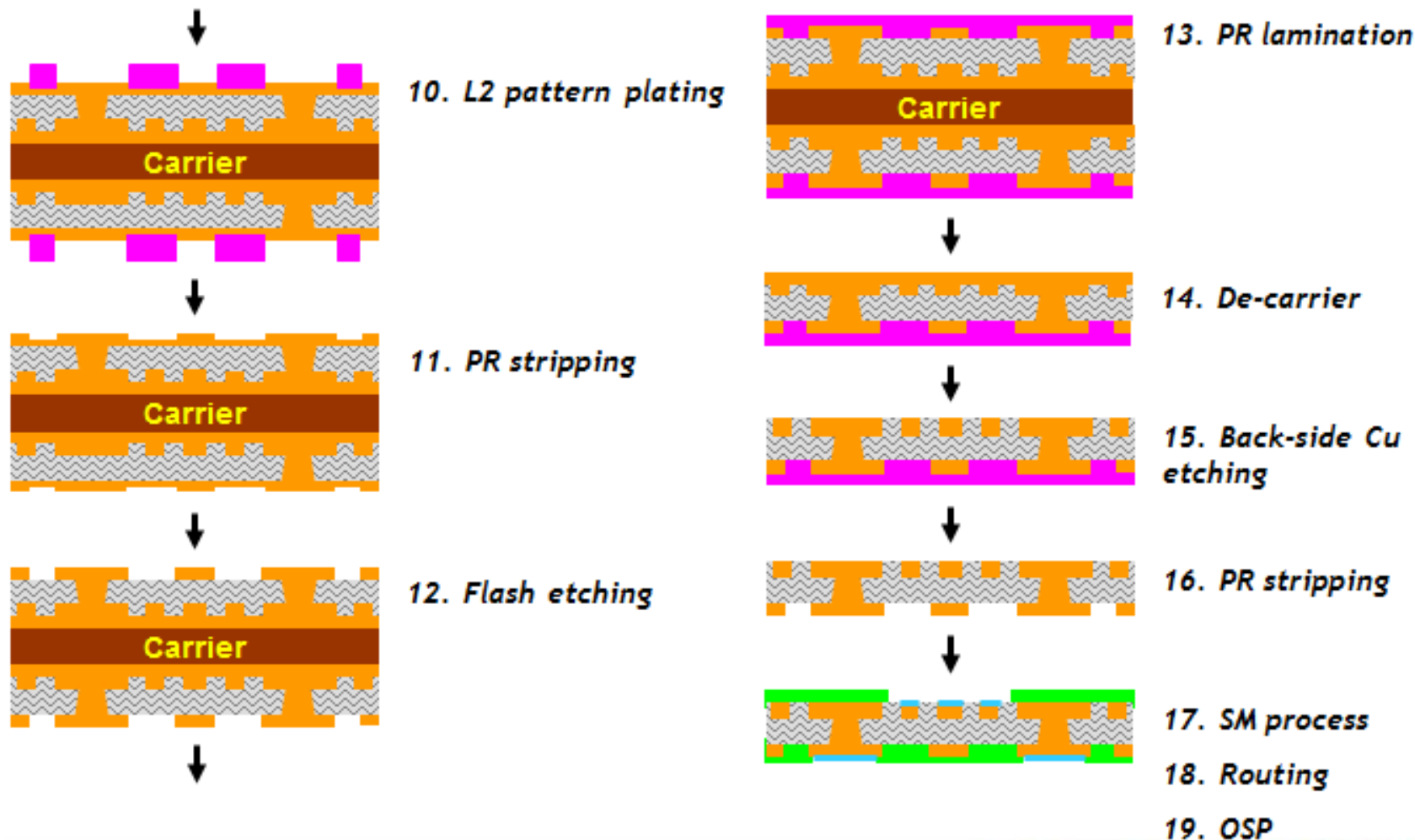
- Pattern plating, Lamination, Via Drill, E'less Cu



# Substrate manufacturing

## ● EPP (Embedded Pattern Process) II

- Pattern plating, Flash Etch, De-carrier, Backside Etch

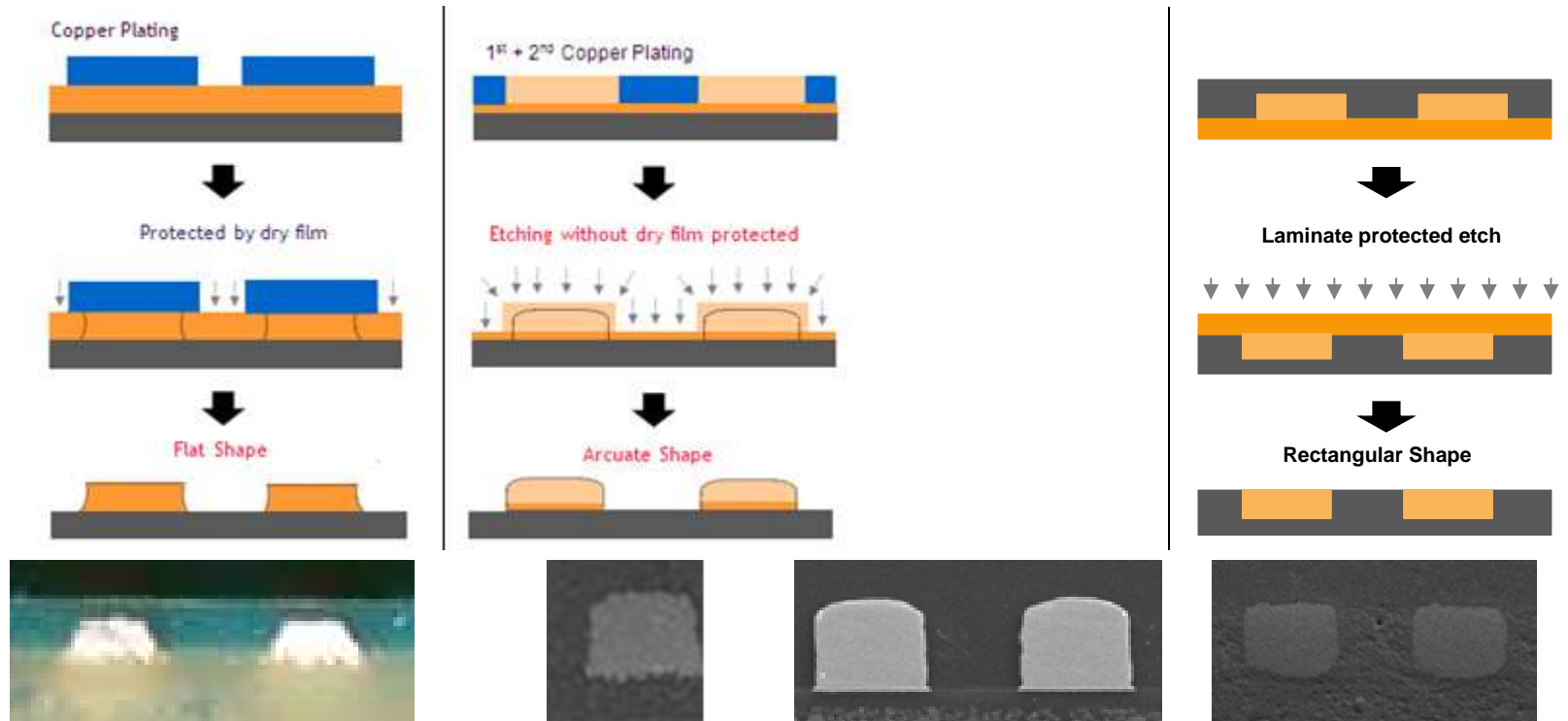




# Substrate manufacturing

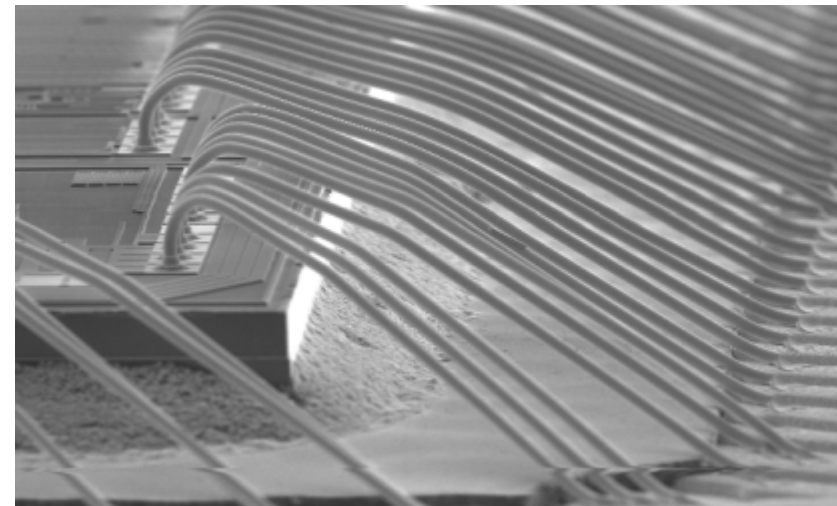
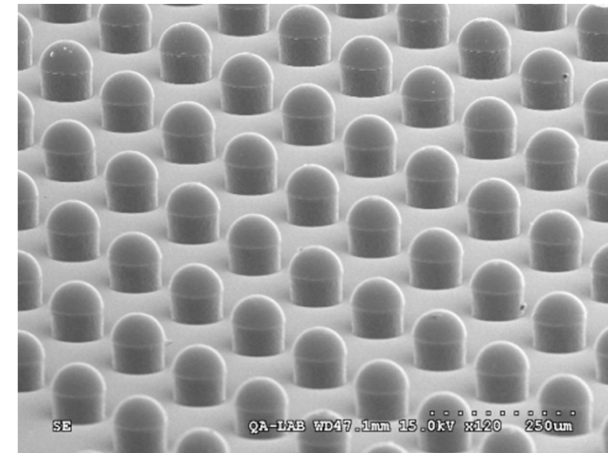
## Subtractive vs. MSAP vs. SAP vs. EPP

Process	Subtractive	MSAP	SAP	EPP
L/S, Pitch	50/50, 100	25/25, 50	20/20, 40	15/15, 30
Top	Flat	Round	Round	Flat
Head Foot Ratio	$(1 - (2/3CuT)) : 1$	1:1	1:1	1:1



# Fine Pitch Bumping

- N40nm / N28nm / N20nm wafer node and beyond
  - Small Die Size
  - High I/O Count
  - Small Pitches
- FC Bumping Pads
- Wire Bond Pads



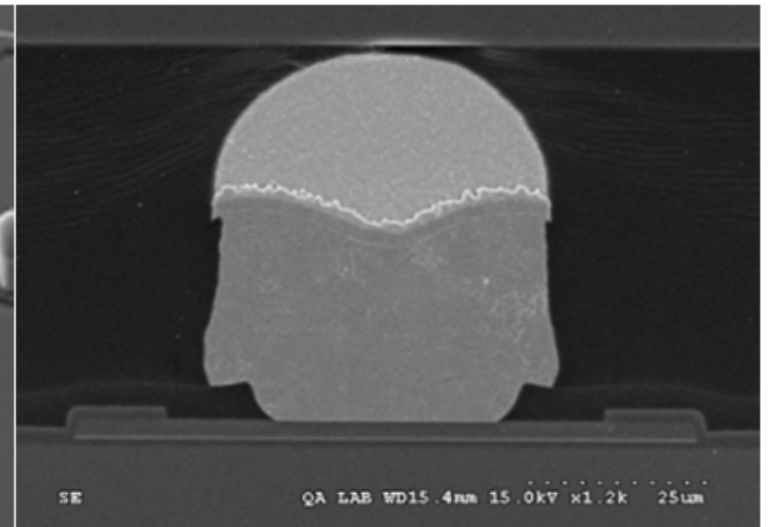
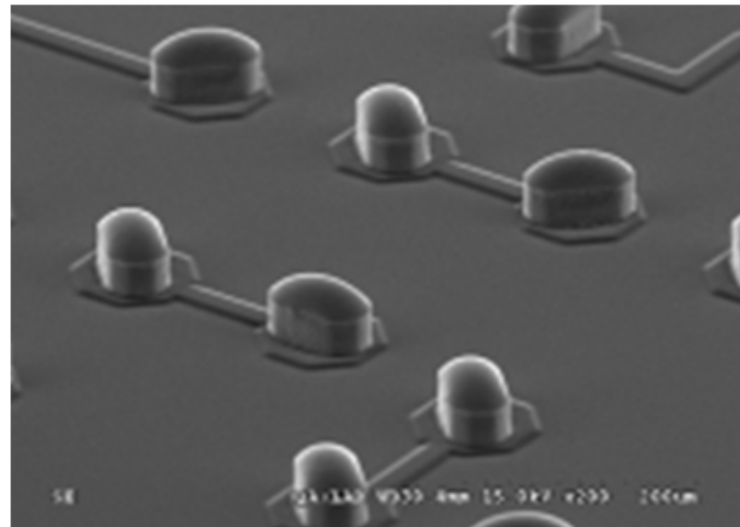
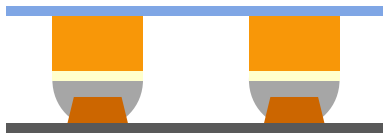
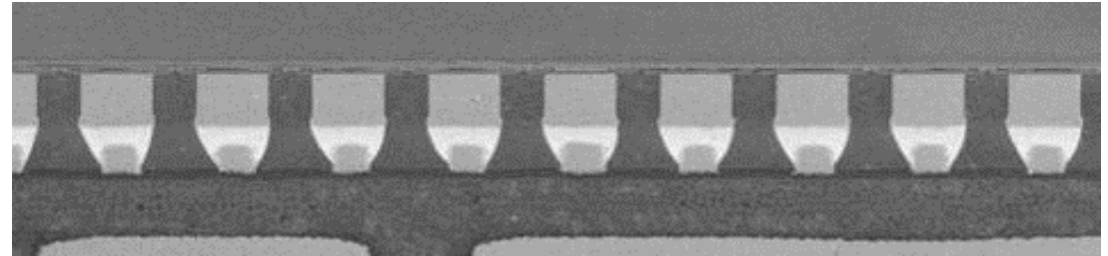
# Fine Pitch Cu Pillar FlipChip

- **CuBOL (Cu Pillar Bond On Line)**

- Solder Cap of Cu Pillar encroaches the Cu Trace on Substrate
- Trace Volume adds to the Solder Cap Volume
- Solder Cap Volume expands

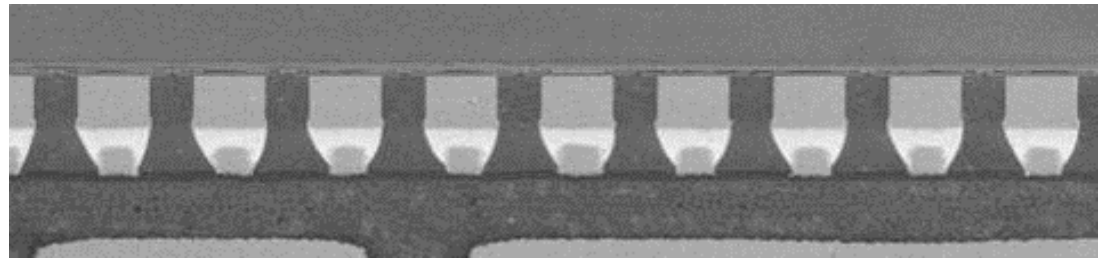
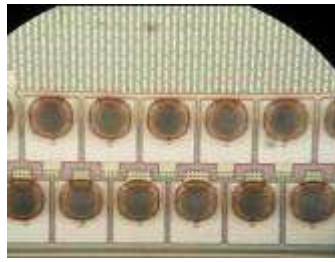
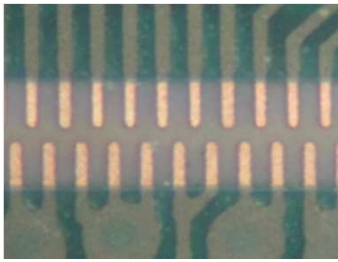
- Along the Trace

- Perpendicular to the Trace

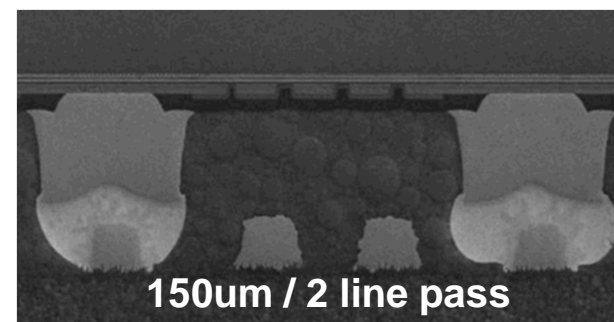
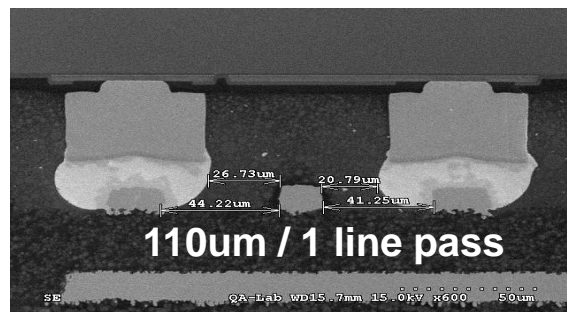


# Fine Pitch Cu Pillar FlipChip

- **FC MR MUF (FlipChip, Mass Reflow, Mold Under Fill)**
  - 2 Rows Peripheral Cu Pillar Bumps 60um Pitch each row



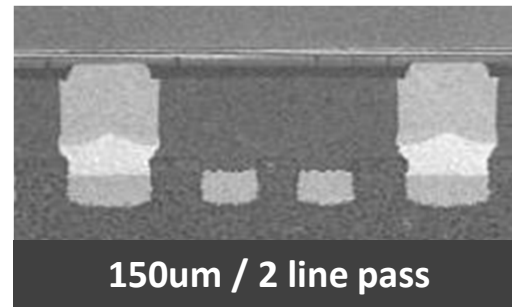
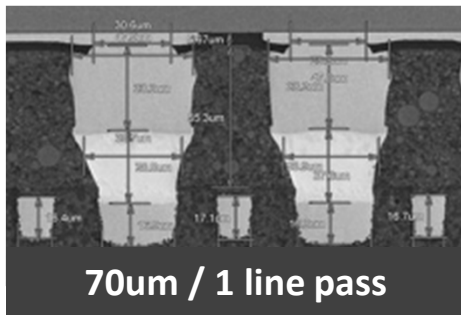
- 3 and more Rows Cu Pillar Bumps have the need of traces routing between bond pads. These traces can not be covered by Solder Mask



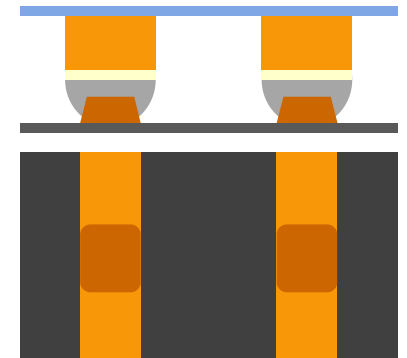
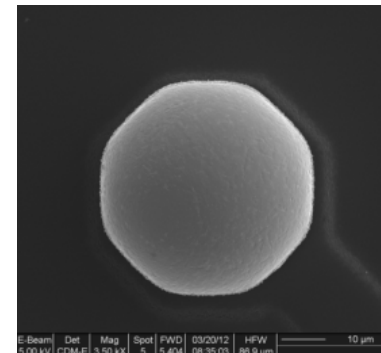
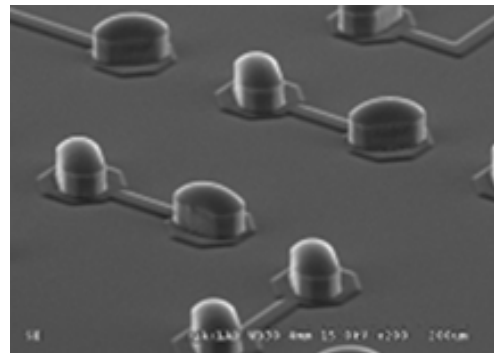
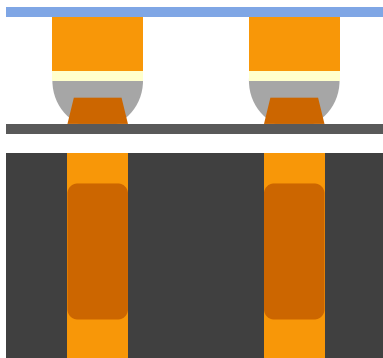
# Fine Pitch Cu Pillar FlipChip

## • CuBOL on EPP Substrate

- Solder Cap of Cu Pillar wets the Cu Trace Top on EPP Substrate
- Trace Volume does not add to the Solder Cap Volume



- **Oval or Bar shape Cu Pillar enlarges the Solder Bond Area**



# Fine Pitch Cu Pillar FlipChip

- **Reliability comparison CuBOL vs. CuBOL EPP Substrate**

- Device 11.8x11.8 mm<sup>2</sup>, 515 Balls, Die 6.6x5 mm<sup>2</sup>,  
899 oval Cu pillar 45x95, pitch 150 um with 2 lines pass

Device Version	MSL3/2aa	TCB 1000 cyc	HAST 96 hrs	TCT 3500 cyc	HTST 3000 hrs
CuBOL	Pass	Pass	Pass	Pass	Pass
CuBOL EPP	Pass	Pass	Pass	Pass	Pass

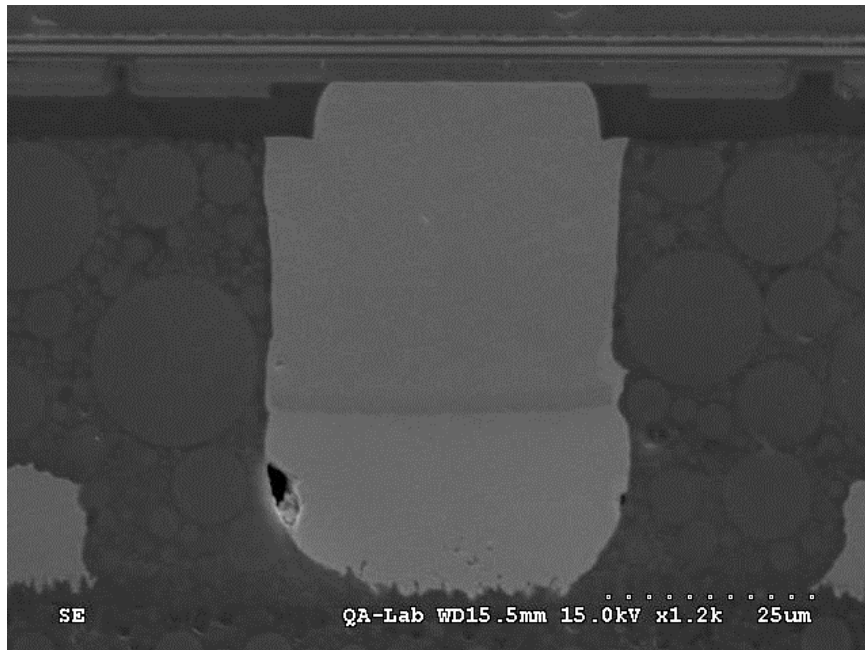




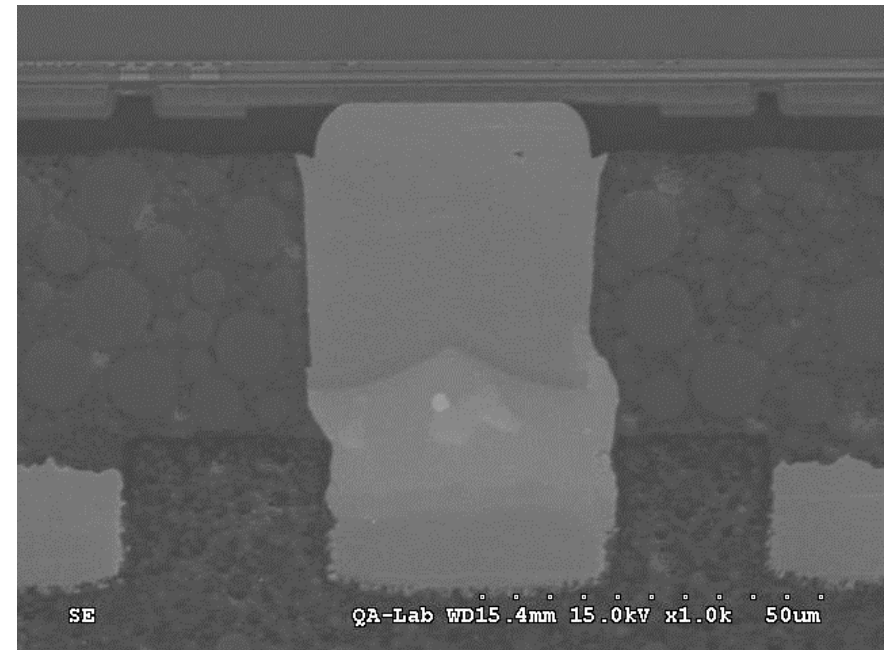
# Fine Pitch Cu Pillar FlipChip

- Reliability comparison CuBOL vs. CuBOL EPP
  - Comparison after TCT 3500 Cycles

**CuBOL –  
Cu Trace no longer observable**



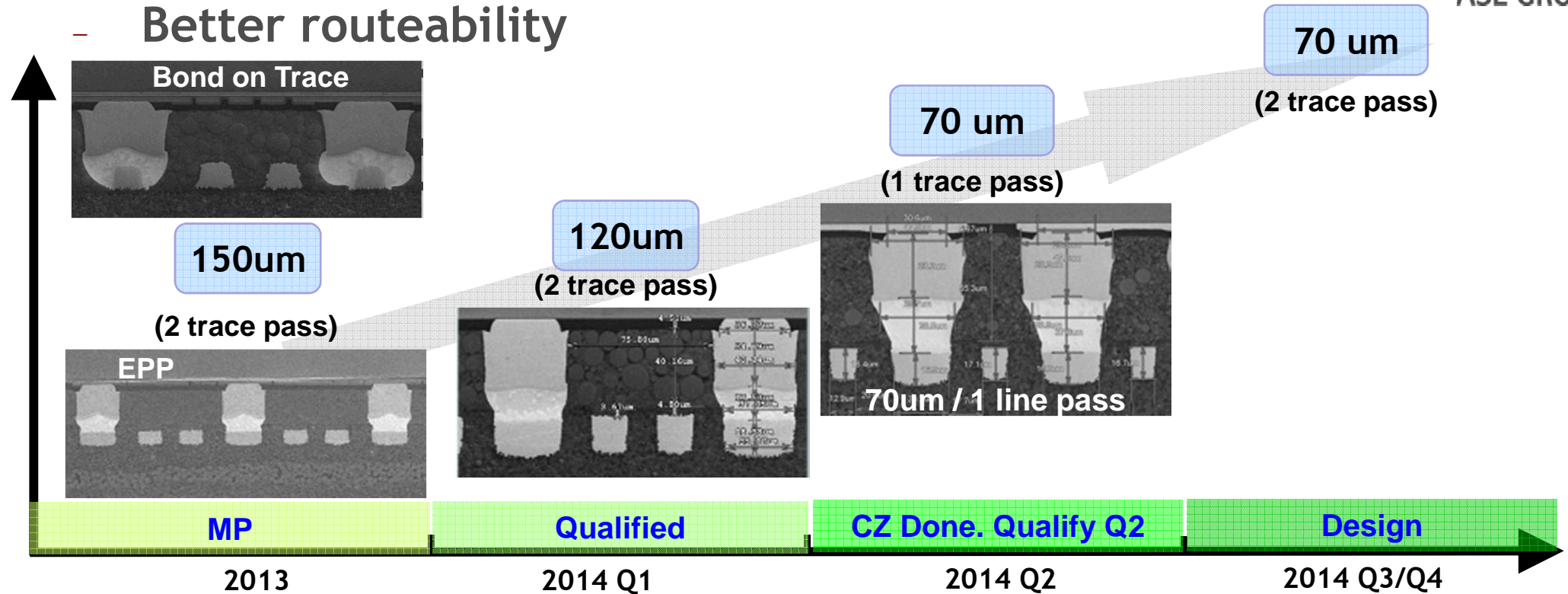
**CuBOL EPP –  
Half of the Cu Trace diluted**



# Cu Pillar Fine Pitch Roadmap

## Advantage of EPP on fine pitch

### Better routeability

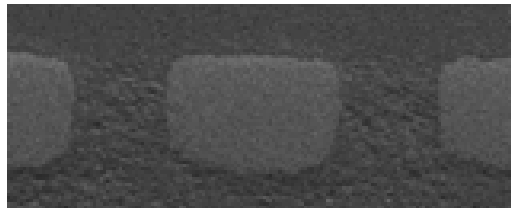
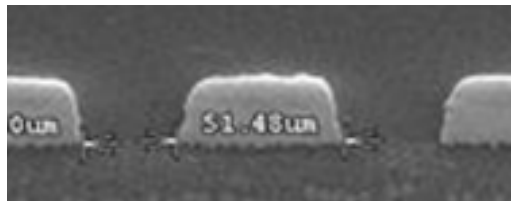
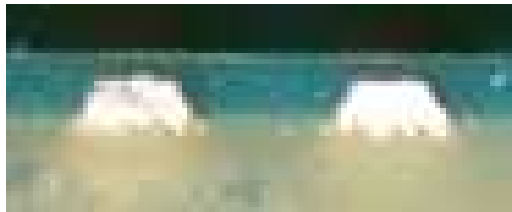
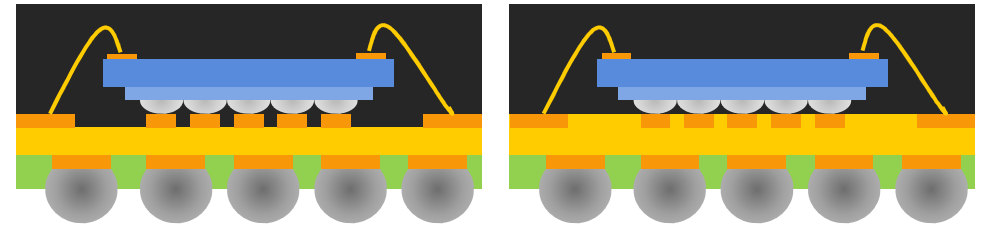


Wafer	28 nm			20 nm	
Process	MR Cu Pillar (BOT / EPP)		MR Cu Pillar (EPP)		
SBS	L/S=20/20	L/S=15/15	L/S=12/12	L/S=10/10	L/S=8/8
C4 Pad	BOT 40	EPP 35		EPP 30	EPP 25
UBM to Trace Space	17.5	15		10	7.5

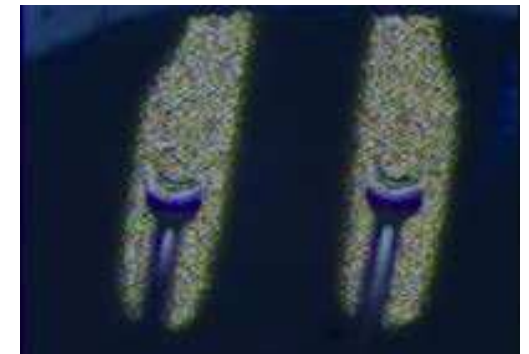
# Bond Finger Pitch

## Hybrid Packages with Wire Bond Die on Top

- Bond Finger Pitch
- Bond Finger Top Width



Process	Head	Foot	Pitch
Sub	40	55	85
MSAP	40	50	80
EPP	40	40	60



# Conclusion



- **EPP Substrates as a result of coreless substrates can be manufactured in any layer count with flexible via connections from layer to layer – high routability**
- **Embedded Traces result in finer pitches for Cu pillar FC assembly as well as for wire bond and hybrid assembly**
- **Slower IMC formation due to only one contact surface to the Copper Pillar solder cap; expect similar reliability test results**
- **EPP Substrates can be a good solution when ultra fine pitch Cu Pillar Flip Chip is requested.**



# Thank You

[www.aseglobal.com](http://www.aseglobal.com)